

CLAIMS

Claims 1 and 2 (Cancelled).

3. (Previously Presented) A method for manufacturing a reflection type liquid crystal display, comprising:

forming plural scanning lines and plural signal lines crossing said scanning lines on an insulating substrate;

forming a switching element in each of picture element regions divided by said scanning lines and said signal lines;

forming an interlayer insulating film having appropriate unevenness of an inseparable pattern in the picture element region and having a contact hole of a separable pattern on a drain electrode of said switching element by plainly applying a photosensitive insulating resin on said substrate so as to dissolve difference in level caused by said scanning lines, said signal lines, and said switching element, and conducting exposure and development while changing an amount of exposure; and

forming a reflex picture element electrode having unevenness due to said interlayer insulating film at a position conforming to each of the picture element regions and which is electrically connected to said switching element through said contact hole, by patterning after forming a high reflex film on said interlayer insulating film, wherein

in the process of forming the interlayer insulating film, a mask is used in exposing the insulating resin and has a shading material comprised of at least two layers, the at least two layers including an ultraviolet filter layer for cutting ultraviolet rays at a predetermined value of

20 to 80 % in a base material, and said ultraviolet filter layer is laid in a mask pattern opening portion located conforming to the picture element region, and

the exposure for forming unevenness on the interlayer insulation film is conducted only from a front side

Claim 4 (Cancelled).

5. (Previously Presented) A mask for manufacturing a reflection type liquid crystal display,

the liquid crystal display being formed of: a first insulating substrate provided with scanning lines and signal lines formed into a lattice configuration, a TFT, an interlayer insulating film, and a reflex picture element electrode; a second insulating substrate provided with a color filter and an opposed electrode and arranged opposite to the first insulating substrates;

said interlayer insulating film being formed of a positive type acrylic resin having a sensitivity to i-line of 365nm in wavelength and h-line of 405nm in wavelength;

the mask for exposing said interlayer insulating film comprising a base material and a shading material of at least two layers provided on said base material;

said at least two layers including an ultraviolet filter layer comprising an amorphous Si film of 1nm to 10nm in thickness for cutting ultraviolet rays at a predetermined value of 20 to 80%;

said ultraviolet filter layer being laid in a mask pattern opening portion located conforming to a picture element region.

6. (Original) The mask for manufacturing a reflection type liquid crystal display according to claim 5, wherein an a-Si film is used as the ultraviolet filter layer and a Cr/CrOx film is used as the shading material for completely shading the ultraviolet rays.

Claims 7 through 17 (Cancelled).

18. (Previously Presented) A reflection type liquid crystal display manufactured according to claim 3.

Claim 19 (Cancelled).